



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT  
83388.0002

In re application of:  
Shin TAMATA, et al  
Serial No: 10/090,413  
Filed: February 28, 2002  
For: PROCESS FOR TREATING  
PERFLUORIDES

Art Unit: 2812  
Examiner: Not Assigned

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to:

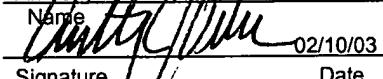
Commissioner for Patents  
Washington D.C. 20231, on

February 10, 2003

Date of Deposit

Anthony J. Olex, Reg. No. 41,232

Name

 02/10/03

Signature

Date

**PRELIMINARY AMENDMENT**

Commissioner for Patents  
Washington, D.C. 20231

Dear Sir:

Prior to the first Office Action in the present application, please enter  
and consider the following amendments and remarks:

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**IN THE SPECIFICATION:**

Please replace the paragraph on pages 1 and 2, starting at line 17 with  
the following text:

In the semiconductor (semiconductor chip and liquid crystal panel) manufacturing plants, perfluorocompounds are used as etching gas or cleaning gas in the semiconductor manufacturing steps. Perfluorocompounds (hereinafter referred to as PFC) are a general term for the chlorine-free compounds of carbon and fluorine, carbon, hydrogen and fluorine, sulfur and fluorine, and nitrogen and fluorine, such as CF<sub>4</sub>, CHF<sub>3</sub>, C<sub>2</sub>F<sub>6</sub>, CH<sub>2</sub>F<sub>2</sub>, C<sub>3</sub>F<sub>8</sub>, C<sub>5</sub>F<sub>8</sub>, SF<sub>6</sub> and NF<sub>3</sub>. PFC have a long life time in the atmosphere (10,000 years for C<sub>2</sub>F<sub>6</sub> and 3,200 years for SF<sub>6</sub>), and they are an earth warming gas with a large warming factor, so that their release into the atmosphere is

regulated. Researchers are pursuing studies on the method of decomposing

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